



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Patricia B. Smith et al. Art Unit: 2823  
Serial No.: 09/199/829 Examiner: Eaton, K.  
Filed: 11/25/98 Docket No.: TI-25250  
For: Hydrogen Plasma Photoresist Strip and Polymeric Residue Cleanup  
Process for Oxygen-Sensitive Materials

#2  
3  
10/18/00

INFORMATION DISCLOSURE STATEMENT

September 28, 2000

Assistant Commissioner for Patents  
Washington, DC 20231

Dear Sir:

Please make the references listed on the enclosed PTO-1449 of record under 37 C.F.R. 1.56, 1.97, and 1.98 in the patent application identified above. Copies of the listed references are enclosed.

Respectfully submitted,

Peter K. McLarty  
Agent for Applicants  
Reg. No. 44923

Texas Instruments Incorporated  
P. O. Box 655474, MS 3999  
Dallas, Texas 75265  
(972) 917-4258

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